

ABSTRACT

Liquid is supplied by a supply mechanism (72) to a space between a lens (42) and a wafer (W) via a supply nozzle(36) on one side of the lens (42), and the liquid is recovered by
5 a recovery mechanism (74) via a recovery pipe (52) on the other side of the lens (42). When the supply and the recovery of the liquid are performed in parallel, a predetermined amount of liquid (exchanged at all times) is held between the lens (42) and the substrate (W) on the stage. Accordingly, when
10 exposure (pattern transfer on the substrate) is performed in this state, an immersion method is applied and a pattern is transferred with good precision onto the substrate. In addition, in the case the liquid leaks out from under the lower edge of a peripheral wall (32g), the liquid that could not
15 be recovered is recovered by an auxiliary recovery mechanism (76) via a slit (32h₃ or 32h₄). And, by such operations, the substrate is freed from the residual liquid on the substrate.



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